IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Seong Hwan Park et al.) I hereby certify that this paper and the documents referred to as enclosed
Serial No.: To be assigned	therewith are being deposited with the United States Postal Service as Express
Filed: November 26, 2003 (Herewith)	 Mail, Airbill No. EV323777167US postage prepaid, on November 26, 2003,
For: Method of Manufacturing Semiconductor Device) in an envelope addressed to) Commissioner for Patents, P.O. Box 1450, Alexandria, Yirginia 22313-1450
Group Art Unit: To be assigned	} Khall
Examiner: To be assigned) Richard Zimmermann
)

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Sir:

Submitted herewith for consideration by the examiner is a copy of the document identified on the attached Form PTO-1449. Entry and consideration of the submitted document is solicited.

The Commissioner is authorized to charge any fee deficiency required by this paper, or credit any overpayment, to Deposit Account No. 13-2855.

Respectfully submitted,

MARSHALL, GERSTEIN & BORUN LLP 6300 Sears Tower 233 South Wacker Drive Chicago, Illinois 60606-6357 (312) 474-6300

November 26, 2003

By:

Michael R. Hull Reg. No. 35,902

For m PTO-1449 (Modified)	U.S. Department of Commerce	Atty. Docket No.	Serial No.	
	Patent and Trademark Office	30205/39511	To be Assigned	
		Applicant		
INFORMATION DISCLOSURE STATEMENT		Seong Hwan Park		
		Filing Date	Group	
		November 26, 2003	To be Assigned	

	U.S. PATENT DOCUMENTS					
*Examiner Initials	Document Number	Issue Date	Name	Class	Subclass	Filing Date if Appropriate

FOREIGN PATENT DOCUMENTS								
*Examiner Initials		Document Number	Publication Date	Country	Class	Subclass	Translati	on ·
							Yes	No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)				
	Fujimura et al., "Ashing of the Ion Implanted Resist Layer," Digest of Papers			
	1989 2 nd MicroProcess Conference, July 2-5, 1989.			

EXAMINER	DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.